

**IN THE CLAIMS**

Please cancel claim 12 without prejudice or disclaimer as to its subject matter and amend claims 1, 2, 5-11 and 13-20 as follows and as follows:

1 1. (Currently Amended) A filter ~~for a plasma display panel~~, comprising:

2 a substrate;

3 a conductive material pattern ~~formed~~ arranged on the substrate, the conductive material  
4 pattern comprising a conductive material, the conductive material having a pattern;

5 a negative photoresist pattern; patterned on the substrate on portions not covered by the  
6 conductive material pattern to complement the conductive material pattern, the negative  
7 photoresist pattern comprising a negative photoresist material that comprises a pigment and a dye  
8 that cuts off light ~~[[in]]~~ of a specific wavelength range, ~~as well as~~ the negative photoresist  
9 material further comprising a material that prevents external light from being reflected; and

10 a plated mesh ~~formed~~ arranged on a conductive material pattern.

1 2. (Currently Amended) The filter of claim 1, the negative photoresist ~~pattern~~ material

2 comprising a material selected from the group consisting of a transparent acryl group and a  
3 phenol group.

1 3. (Original) The filter of claim 1, the dye comprising an organic compound selected from  
2 the group consisting of an imonium group and a phthalocyanin group, the pigment comprising an

organic compound of the imonium group, the dye blocking near infrared rays.

4. (Original) The filter of claim 1, the dye comprising an organic compound selected from the group consisting of an imonium group and a phthalocyanin group, the pigment comprising an organic compound of the imonium group, the dye blocking light having a wavelength near 590 nm.

5. (Currently Amended) The filter of claim 1, ~~[[the]]~~ a combined thickness of the conductive material pattern and the plated mesh ~~formed~~ arranged thereon being in a range of 1 to 50  $\mu\text{m}$ .

6. (Currently Amended) The filter of claim 1, wherein said material ~~preventing the~~ that prevents external light from being reflected being selected from the group consisting of a metal powder and an inorganic metal oxide.

7. (Currently Amended) The filter of claim 1, the filter being formed by a process comprising: ~~A method of manufacturing a filter for a plasma display panel, the method comprising the steps of:~~

coating an entire surface of ~~[[a]]~~ the substrate with a layer of ~~[[a]]~~ the conductive material;

forming a predetermined positive photoresist pattern on the conductive material by

7 applying the photoresist, exposing the photoresist and developing the exposed photoresist;

8 etching exposed portions of the conductive material;

9 removing said patterned positive photoresist leaving a ~~patterned~~ the conductive material  
10 pattern on the substrate;

11 coating said entire surface of the substrate having the ~~patterned~~ conductive material  
12 pattern with a ~~layer of the~~ negative photoresist material ~~that comprises a dye and a pigment that~~  
13 ~~cuts off light in a specific wavelength range, the negative photoresist further comprising a~~  
14 ~~material preventing external light from being reflected;~~

15 exposing the negative photoresist material by illuminating said substrate from a side  
16 opposite from said surface containing said ~~patterned~~ conductive ~~layer~~ material pattern and the  
17 negative photoresist material;

18 developing the exposed negative photoresist material to form ~~[[a]]~~ the negative  
19 photoresist pattern exposing said ~~patterned~~ conductive material pattern; and

20 forming ~~[[a]]~~ the plated mesh on the exposed conductive material pattern by electrical  
21 plating.

1 8. (Currently Amended) The ~~method~~ filter of claim 7, wherein the negative photoresist  
2 material comprises a material selected from the group consisting of a transparent acryl group and  
3 a phenol group.

1 9. (Currently Amended) The ~~method~~ filter of claim 7, the dye comprises an organic

2 compound of an imonium group, and the pigment comprises an organic compound of the  
3 imonium group, the dye filtering out near infrared rays.

1 10. (Currently Amended) The ~~method~~ filter of claim 7, wherein the dye is an organic  
2 compound of an imonium group or a phthalocyanin group, and the pigment is an organic  
3 compound of the imonium group, the dye blocking light having a wavelength of about 590 nm.

1 11. (Currently Amended) The filter of claim 1, the filter being formed by a process  
2 comprising: A method for making a filter for a plasma display panel, comprising the steps of:

3 forming the ~~a patterned layer of~~ a conductive material pattern on ~~one~~ a first side of a  
4 ~~transparent~~ the substrate;

5 applying a layer of the negative photoresist material on said ~~patterned~~ first side of said  
6 substrate;

7 exposing a pattern in said layer of negative photoresist material by illuminating a side of  
8 said substrate opposite said ~~patterned~~ first side;

9 developing said layer of negative photoresist material resulting in said negative  
10 photoresist pattern ~~exposing only portions on said one side of said substrate patterned by the~~  
11 ~~conductive material; and~~

12 increasing ~~[[the]]~~ a thickness of said conductive material pattern on said first ~~on said one~~  
13 side of said substrate by electroplating.

1 Claim 12 (Canceled)

1 13. (Currently Amended) The ~~method~~ filter of claim 11, said ~~patterned~~ conductive  
2 material pattern being formed by a process comprising:

3 forming a blanket layer of the conductive material;

4 applying, patterning, and developing a positive photoresist layer on the blanket  
5 ~~conductive layer~~ of conductive material;

6 then etching the blanket layer of conductive material ~~layer~~ with patterned photoresist  
7 thereon; and then ~~before~~

8 removing the patterned positive photoresist.

1 14. (Currently Amended) The ~~method~~ filter of claim 13, said blanket layer of conductive  
2 material being formed by sputtering.

1 15. (Currently Amended) The ~~method~~ filter of claim 11, the process further comprising  
2 adding additives to said negative photoresist prior to said applying step, the additives ~~serving~~  
3 being adapted to filter out near infrared wavelengths.

1 16. (Currently Amended) The ~~method~~ filter of claim 11, said conductive material pattern  
2 adapted to serve ~~patterned layer of said conductive material serves~~ as a mask in said exposing  
3 step.

1 17. (Currently Amended) A filter ~~for a plasma display~~, comprising:  
2 a substrate that is transparent to light;  
3 a conductive mesh pattern arranged ~~formed~~ on one side of the substrate; and  
4 a non conductive material ~~disposed~~ arranged on said one side of said substrate at  
5 locations absent said conductive mesh.

1 18. (Currently Amended) The filter of claim 17, said conductive mesh pattern and said  
2 non-conductive material having equal depths between 1 and 50 microns.

1 19. (Currently Amended) The filter of claim 17, said non conductive material ~~being~~  
2 comprising negative photoresist ~~containing~~ comprising additives.

1 20. (Currently Amended) The filter of claim 17, said conductive mesh pattern being  
2 electrically grounded.

1 21. (Currently Amended) The filter of claim 17, said conductive mesh pattern having a  
2 grid pattern.

1 22. (Currently Amended) The filter of claim ~~[[17]]~~ 19, said additives comprising a dye.